

CAMT Seminar

“Challenges of Plasma-Surface Interactions in Semiconductor Manufacturing”

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Date: March 7, 2018 (Wednesday) 14:00-15:00

Location: Main Conference Room (1st floor), Bldg. A12
Center for Atomic and Molecular Technologies (CAMT)
(A12 棟 1 階会議室)

Abstract:

Plasma-surface interactions are still poorly understood even after many years of study and investigation. For example, the issue of the ways that plasma alter surface texture - like roughness - are only now beginning to be addressed. In industrial practice, effects such as pulsing and attempts to develop and use atomic layer etching are challenging our fundamental understanding of how plasmas alter surfaces through a combination of chemical and physical effects. The effects of ions and neutrals can be dramatically altered by gas pressure and ion collisions in sheaths as well. In this talk, I will outline and summarize some key areas that need further investigation in plasma-surface interactions for semiconductor processing.

(Host: Satoshi Hamaguchi Ext:7913)